| L Number | Hits | Search Text                                      | DB                     | Time stamp       |
|----------|------|--|------------------------|------------------|
|          | 288  | (low adj k adj dielectric low-k-dielectric       | USPAT;                 | 2004/02/17 13:18 |
|          |      | low-k adi dielectric ((low adj k low-k) adj      | US-PGPUB;              |                  |
|          |      | material)) and (etch\$3 plasma) and (nitrogen    | EPO; JPO;              |                  |
|          |      | N2 "n.sub.2") and (fluorocarbon                  | DERWENT;               |                  |
|          | •    | hydrofluorocarbon C4F6 C5F8 C4F8 CF2H2 CH2F2     | IBM_TDB                |                  |
|          |      | "C.sub.4 F.sub.6" "C.sub.5 F.sub.8" "C.sub.4     | 1                      |                  |
|          |      | F.sub.8" "CF.sub.2 H.sub.2" "CH.sub.2            |                        |                  |
|          |      | F.sub.2")  |                        | 2003/09/14 16:14 |
| -        | 18   | ((low adj k adj dielectric low-k-dielectric      | USPAT;                 | 2003/09/14 18:14 |
|          |      | low-k adj dielectric ((low adj k low-k) adj      | US-PGPUB;              |                  |
|          |      | material)) and (etch\$3 plasma) and (nitrogen    | EPO; JPO;              |                  |
|          |      | N2 "n.sub.2") and (fluorocarbon                  | DERWENT;               |                  |
|          |      | hydrofluorocarbon C4F6 C5F8 C4F8 CF2H2 CH2F2     | IBM_TDB                |                  |
|          |      | "C.sub.4 F.sub.6" "C.sub.5 F.sub.8" "C.sub.4     |                        |                  |
|          |      | F.sub.8" "CF.sub.2 H.sub.2" "CH.sub.2            |                        |                  |
|          |      | F.sub.2") ) and etch\$3 same (low adj k adj      |                        |                  |
|          | •    | dielectric low-k-dielectric low-k adj            |                        |                  |
|          |      | dielectric ((low adj k low-k) adj material))     | 1                      |                  |
|          |      | same ((nitrogen N2 "n.sub.2") with               |                        |                  |
|          |      | (fluorocarbon hydrofluorocarbon C4F6 C5F8        |                        |                  |
|          |      | C4F8 CF2H2 CH2F2 "C.sub.4 F.sub.6" "C.sub.5      |                        |                  |
|          | •    | F.sub.8" "C.sub.4 F.sub.8" "CF.sub.2             |                        |                  |
|          |      | H.sub.2" "CH.sub.2 F.sub.2"))                    | HCDAT.                 | 2004/02/06 20:10 |
|          | 71   | etch\$3 with (low adj k low-k BCB SiLk) and      | USPAT;                 | 2004/02/00 20:10 |
|          |      | (oxygen-free oxygen adj free ((02 "O.sub.2"      | US-PGPUB;              |                  |
|          |      | oxygen) near (without free)))                    | EPO; JPO;              |                  |
|          |      |  | DERWENT;               |                  |
|          |      |  | IBM_TDB                | 2004/02/06 19:58 |
|          | 19   | etch\$3 with (low adj k low-k BCB SiLk) same     | USPAT;                 | 2004/02/06 19:58 |
|          |      | (oxygen-free oxygen adj free ((02 "0.sub.2"      | US-PGPUB;              |                  |
|          |      | oxygen) near (without free)))                    | EPO; JPO;              |                  |
|          |      |  | DERWENT;               |                  |
|          |      | and the same of the said has been distributed by | IBM_TDB                | 2004/02/06 19:25 |
|          | 9    | etch\$3 with (low adj k low-k BCB SiLk) with     | USPAT;                 | 2004/02/06 19.23 |
|          |      | (oxygen-free oxygen adj free ((02 "O.sub.2"      | US-PGPUB;<br>EPO; JPO; |                  |
|          |      | oxygen) near (without free)))                    |                        |                  |
|          | *    |  | DERWENT;<br>IBM TDB    |                  |
|          |      | ( ) to () () and le long Cills comp              | USPAT;                 | 2004/02/06 19:25 |
| -        | 10   | (etch\$3 with (low adj k low-k BCB SiLk) same    | US-PGPUB;              | 2004/02/00 13.23 |
|          | Ì    | (oxygen-free oxygen adj free ((02 "0.sub.2"      | 1                      |                  |
|          |      | oxygen) near (without free)))) not (etch\$3      | EPO; JPO;              |                  |
|          |      | with (low adj k low-k BCB SiLk) with             | DERWENT;               |                  |
|          |      | (oxygen-free oxygen adj free ((02 "0.sub.2"      | IBM_TDB                | - 1              |
|          |      | oxygen) near (without free))))                   | HCDAT.                 | 2004/02/06 20:08 |
|          | 6    | etch\$3 same (low adj k low-k BCB SiLk) same     | USPAT;                 | 2004/02/00 20:00 |
|          |      | (oxygen-free oxygen adj free ((02 "O.sub.2"      | US-PGPUB;<br>EPO; JPO; |                  |
|          |      | oxygen) near (without free))) not (etch\$3       |                        |                  |
|          |      | with (low adj k low-k BCB SiLk) same             | DERWENT;<br>IBM_TDB    |                  |
|          |      | (oxygen-free oxygen adj free ((02 "O.sub.2"      | TD: 1 TDD              | •                |
|          |      | oxygen) near (without free))))                   | USPAT;                 | 2004/02/06 20:09 |
| -        | 81   | etch\$3 same (low adj k low-k BCB SiLk) and      | US-PGPUB;              | 2301,02,00 20.09 |
|          |      | (oxygen-free oxygen adj free ((02 "O.sub.2"      | EPO; JPO;              |                  |
|          |      | oxygen) near (without free))) not (etch\$3       | DERWENT;               |                  |
|          |      | with (low adj k low-k BCB SiLk) same             | IBM TDB                |                  |
|          |      | (oxygen-free oxygen adj free ((02 "O.sub.2"      | TEN_IDE                |                  |
|          |      | oxygen) near (without free))))                   | HCDAT.                 | 2004/02/06 20:09 |
|          | 2    | etch\$3 same (low adj k low-k BCB SiLk) with     | USPAT;                 | 2004/02/00 20:03 |
|          |      | (oxygen-free oxygen adj free ((02 "0.sub.2"      | US-PGPUB;              |                  |
|          |      | oxygen) near (without free))) not (etch\$3       | EPO; JPO;              |                  |
| ć        |      | with (low adj k low-k BCB SiLk) same             | DERWENT;               |                  |
| *        |      | (oxygen-free oxygen adj free ((O2 "O.sub.2"      | IBM_TDB                |                  |
|          |      | oxygen) near (without free))))                   | HODAM                  | 2004/02/06 20:11 |
| _        | 36   | etch\$3 near (low adj k low-k BCB SiLk) and      | USPAT;                 | 2004/02/06 20:11 |
|          | 1    | (oxygen-free oxygen adj free ((O2 "O.sub.2"      | US-PGPUB;              |                  |
|          |      | oxygen) near (without free)))                    | EPO; JPO;              |                  |
|          | 8    |  | DERWENT;<br>IBM TDB    |                  |
|          |      |  |                        |                  |

|     |    | (1 di la lou la DCD Silk) and                 | USPAT;   | 2004/02/06 | 20.40 |
|-----|----|---|--|------------|-------|
| - , | 24 | (etch\$3 near (low adj k low-k BCB SiLk) and  | US-PGPUB;  | 2004/02/08 | 20.40 |
|     |    | (oxygen-free oxygen adj free ((02 "O.sub.2"   | The state of the s |            |       |
|     |    | oxygen) near (without free)))) not ((etch\$3  | EPO; JPO;  |            |       |
|     |    | with (low adj k low-k BCB SiLk) same          | DERWENT;   |            |       |
|     |    | (oxygen-free oxygen adj free ((02 "O.sub.2"   | IBM_TDB  |            |       |
|     |    | oxygen) near (without free)))) (etch\$3 with  |  |            |       |
|     |    | (low adj k low-k BCB SiLk) with (oxygen-free  |  |            |       |
|     |    | oxygen adj free ((O2 "O.sub.2" oxygen) near   |  |            |       |
|     |    | (without free)))) ((etch\$3 with (low adj k   |  |            |       |
|     |    | low-k BCB SiLk) same (oxygen-free oxygen adj  |  |            |       |
|     |    | free ((O2 "O.sub.2" oxygen) near (without     |  |            |       |
|     |    | free)))) not (etch\$3 with (low adj k low-k   |  |            |       |
|     |    | BCB SiLk) with (oxygen-free oxygen adj free   |  |            |       |
|     |    | ((O2 "O.sub.2" oxygen) near (without          |  |            |       |
|     |    | free))))) (etch\$3 same (low adj k low-k BCB  |  |            |       |
|     |    | SiLk) same (oxygen-free oxygen adj free ((O2  |  |            |       |
|     |    | "O.sub.2" oxygen) near (without free))) not   |  |            |       |
|     | *  | (etch\$3 with (low adj k low-k BCB SiLk) same |  |            |       |
|     |    | (oxygen-free oxygen adj free ((02 "0.sub.2"   |  |            |       |
|     |    | oxygen) near (without free))))) (etch\$3 same |  |            |       |
|     |    | (low adj k low-k BCB SiLk) with (oxygen-free  |  |            |       |
|     |    | oxygen adj free ((O2 "O.sub.2" oxygen) near   |  |            |       |
|     |    | (without free))) not (etch\$3 with (low adj k |  |            |       |
|     |    | low-k BCB SiLk) same (oxygen-free oxygen adj  |  |            |       |
|     | ŀ  | free ((02 "0.sub.2" oxygen) near (without     |  |            |       |
|     |    | free))))))                                    |  |            |       |

| 24 | (etch\$3 with (low adj k low-k BCB SiLk) and (oxygen-free oxygen adj free ((O2 "O.sub.2" oxygen) near (without free))) not ((etch\$3 with (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((O2 "O.sub.2" oxygen) near (without free)))) (etch\$3 with (low adj k low-k BCB SiLk) with (oxygen-free oxygen adj free ((O2 "O.sub.2" oxygen) near (without free)))) ((etch\$3 with (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((O2 "O.sub.2" oxygen) near (without free)))) not (etch\$3 with (low adj k low-k BCB SiLk) with (oxygen-free oxygen adj free ((O2 "O.sub.2" oxygen) near (without free)))) (etch\$3 same (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((O2 "O.sub.2" oxygen) near (without free)))) ot (etch\$3 same (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((O2 "O.sub.2" oxygen) near (without free)))) (etch\$3 same (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((O2 "O.sub.2" oxygen) near (without free)))) (etch\$3 same (low adj k low-k BCB SiLk) with (oxygen-free oxygen adj free ((O2 "O.sub.2" oxygen) near (without free)))) (etch\$3 near (low adj k low-k BCB SiLk) and (oxygen-free oxygen adj free ((O2 "O.sub.2" oxygen) near (without free)))) (etch\$3 near (low adj k low-k BCB SiLk) and (oxygen-free oxygen adj free ((O2 "O.sub.2" oxygen) near (without free)))) (etch\$3 mear (low adj k low-k BCB SiLk) and (oxygen-free oxygen adj free ((O2 "O.sub.2" oxygen) near (without free)))) (etch\$3 with (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((O2 "O.sub.2" oxygen) near (without free)))) (etch\$3 with (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((O2 "O.sub.2" oxygen) near (without free)))) (etch\$3 with (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((O2 "O.sub.2" oxygen) near (without free)))) not (etch\$3 with (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((O2 "O.sub.2" oxygen) near (without free))) not (etch\$3 with (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((O2 "O.sub.2" oxygen) near (without | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/02/06 | 20:54 |
|----|--|---|------------|-------|
| *  | (without free))) not (etch\$3 with (low adj k low-k BCB SiLk) same (oxygen-free oxygen adi   |   | ė          |       |
|    | free ((O2 "O.sub.2" oxygen) near (without free))))))))   | 1   |            |       |

(etch\$3 same (low adj k low-k BCB SiLk) and 2004/02/06 20:54 USPAT; (oxygen-free oxygen adj free ((02 "0.sub.2" US-PGPUB; oxygen) near (without free))) not (etch\$3 EPO; JPO; with (low adj k low-k BCB SiLk) same DERWENT: (oxygen-free oxygen adj free ((02 "0.sub.2" IBM TDB oxygen) near (without free))))) not ((etch\$3 with (low adj k low-k BCB SiLk) and (oxygen-free oxygen adj free ((02 "0.sub.2" oxygen) near (without free)))) (etch\$3 with (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((O2 "O.sub.2" oxygen) near (without free)))) (etch\$3 with (low adj k low-k BCB SiLk) with (oxygen-free oxygen adj free ((O2 "O.sub.2" oxygen) near (without free)))) ((etch\$3 with (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((O2 "O.sub.2" oxygen) near (without free)))) not (etch\$3 with (low adj k low-k BCB SiLk) with (oxygen-free oxygen adj free ((02 "0.sub.2" oxygen) near (without free))))) (etch\$3 same (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((O2 "O.sub.2" oxygen) near (without free))) not (etch\$3 with (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((O2 "O.sub.2" oxygen) near (without free))))) (etch\$3 same (low adj k low-k BCB SiLk) with (oxygen-free oxygen adj free ((O2 "O.sub.2" oxygen) near (without free))) not (etch\$3 with (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((02 "0.sub.2" oxygen) near (without free))))) (etch\$3 near (low adj k low-k BCB SiLk) and (oxygen-free oxygen adj free ((02 "O.sub.2" oxygen) near (without free)))) ((etch\$3 near (low adj k low-k BCB SiLk) and (oxygen-free oxygen adj free ((02 "0.sub.2" oxygen) near (without free)))) not ((etch\$3 with (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((02 "O.sub.2" oxygen) near (without free)))) (etch\$3 with (low adj k low-k BCB SiLk) with (oxygen-free oxygen adj free ((O2 "O.sub.2" oxygen) near (without free)))) ((etch\$3 with (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((O2 "O.sub.2" oxygen) near (without free)))) not (etch\$3 with (low adj k low-k BCB SiLk) with (oxygen-free oxygen adj free ((02 "0.sub.2" oxygen) near (without free))))) (etch\$3 same (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((02 "O.sub.2" oxygen) near (without free))) not (etch\$3 with (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((02 "0.sub.2" oxygen) near (without free))))) (etch\$3 same (low adj k low-k BCB SiLk) with (oxygen-free oxygen adj free ((O2) "O.sub.2" oxygen) near (without free))) not (etch\$3 with (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((02 "0.sub.2"

oxygen) near (without free))))))))

(etch\$3 same (low adj k low-k BCB SiLk) and (oxygen-free oxygen adj free ((02 "0.sub.2" oxygen) near (without free))) not (etch\$3 with (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((02 "0.sub.2" oxygen) near (without free))))) not ((etch\$3 with (low adj k low-k BCB SiLk) and (oxygen-free oxygen adj free ((02 "O.sub.2" oxygen) near (without free)))) (etch\$3 with (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((02 "O.sub.2" oxygen) near (without free)))) (etch\$3 with (low adj k low-k BCB SiLk) with (oxygen-free oxygen adj free ((O2 "O.sub.2" oxygen) near (without free)))) ((etch\$3 with (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((02 "O.sub.2" oxygen) near (without free)))) not (etch\$3 with (low adj k low-k BCB SiLk) with (oxygen-free oxygen adj free ((02 "O.sub.2" oxygen) near (without free))))) (etch\$3 same (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((02 "O.sub.2" oxygen) near (without free))) not (etch\$3 with (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((02 "O.sub.2" oxygen) near (without free))))) (etch\$3 same (low adj k low-k BCB SiLk) with (oxygen-free oxygen adj free ((02) "O.sub.2" oxygen) near (without free))) not (etch\$3 with (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((O2 "O.sub.2" oxygen) near (without free))))) (etch\$3 near (low adj k low-k BCB SiLk) and (oxygen-free oxygen adj free ((02 "O.sub.2" oxygen) near (without free)))) ((etch\$3 near (low adj k low-k BCB SiLk) and (oxygen-free oxygen adj free ((02 "0.sub.2" oxygen) near (without free)))) not ((etch\$3 with (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((02 "O.sub.2" oxygen) near (without free)))) (etch\$3 with (low adj k low-k BCB SiLk) with (oxygen-free oxygen adj free ((O2 "O.sub.2" oxygen) near (without free)))) ((etch\$3 with (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((O2 "O.sub.2" oxygen) near (without free)))) not (etch\$3 with (low adj k low-k BCB SiLk) with (oxygen-free oxygen adj free ((02 "O.sub.2" oxygen) near (without free))))) (etch\$3 same (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((02 "O.sub.2" oxygen) near (without free))) not (etch\$3\$ with (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((02 "O.sub.2" oxygen) near (without free))))) (etch\$3 same (low adj k low-k BCB SiLk) with (oxygen-free oxygen adj free ((02 "O.sub.2" oxygen) near (without free))) not (etch\$3 with (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((02 "O.sub.2" oxygen) near (without free))))))) ((etch\$3 with (low adj k low-k BCB SiLk) and (oxygen-free oxygen adj free ((02 "O.sub.2" oxygen) near (without free)))) not ((etch\$3 with (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((02 "O.sub.2" oxygen) near (without free)))) (etch\$3 with (low adj k low-k BCB SiLk) with (oxygen-free oxygen adj free ((O2 "O.sub.2" oxygen) near (without free)))) ((etch\$3 with (low adj k low-k BCB SiLk) same (oxygen-free oxygen adj free ((02 "0.sub.2" oxygen) near (without free)))) not (etch\$3 with (low adj k low-k BCB SiLk) with (oxygen-free oxygen adj free

USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM\_TDB 2004/02/06 20:54

|   |    |   | T         | 0004/00/17 15 10   |
|---|----|---|-----------|--------------------|
| - | 12 | (low adj k low-k low adj dielectric) and      | USPAT;    | 2004/02/17 15:18   |
|   |    | (etch\$3 plasma) and ((nitrogen N2 "N.sub.2") | US-PGPUB; |                    |
| ĺ |    | same (C4F8 "C.sub.4 F.sub.8") same            | EPO; JPO; |                    |
|   |    | ("CF.sub.2 H.sub.2" "CH.sub.2 F.sub.2" CF2H2  | DERWENT;  |                    |
|   |    | CH2F2))                                       | IBM TDB   |                    |
|   | 13 | (low adj k low-k low adj dielectric) and      | USPAT;    | 2004/02/17 13:55   |
| - | 13 | (etch\$3 plasma) and ((nitrogen N2 "N.sub.2") | US-PGPUB; | 1                  |
|   |    | same (C5F8 "C.sub.5 F.sub.8") same (Ar        | EPO; JPO; |                    |
|   |    | argon))                                       | DERWENT;  |                    |
| 1 |    | argon, i                                      | IBM TDB   |                    |
|   | 23 | high adj density with MORI                    | USPAT;    | 2004/02/17 15:09   |
| - | 23 | nigh adj density with Mori                    | US-PGPUB; | 2003, 02, 21 21 33 |
|   |    |   | EPO; JPO; |                    |
|   |    |   | DERWENT;  | 1                  |
|   |    |   | IBM TDB   |                    |
|   |    |   | -         | 2004/02/17 15:12   |
| - | 15 | ("4512868"   "4609428"   "4859303"            | USPAT     | 2004/02/17 15:12   |
|   |    | "4971653"   "4985109"   "4985112"             |           |                    |
|   |    | "4990229"   "5024748"   "5091049"             |           |                    |
|   |    | "5114529"   "5122251"   "5242536"             |           |                    |
|   |    | "5336366" "5385624" "5449433").PN.            |           |                    |